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Low-Energy Electron Potentiometry

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Highlights

- Electronic properties of surfaces are mapped out by low-energy electron microscopy
- High lateral resolution, a large field of view and fast data acquisition is achieved
- Virtually, any sample can be studied using low-energy electron potentiometry
- Intrinsic, lateral workfunction variations are studied in detail
- Lateral properties of Schottky contacts on metal-silicon interfaces are resolved

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